

PATENT NUMBER

U.S. UTILITY Patent Application

O.I.P.E.

PATENT DATE

SCANNED

Q.A.

APPLICATION NO.
09/596637

CONT/PRIOR

CLASS

SUBCLASS

ART UNIT

EXAMINER

APPLICANTS

TITLE

Method for fabricating microstructures with deep anisotropic etching of thick silicon wafers

PTO-2040
12/99

ISSUING CLASSIFICATION

ORIGINAL					CROSS REFERENCE(S)						
CLASS		SUBCLASS			CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)					
438					438						
INTERNATIONAL CLASSIFICATION											
H01L		21/302									

<input type="checkbox"/> TERMINAL DISCLAIMER	DRAWINGS		CLAIMS ALLOWED	
	Sheets Drwg. 18	Figs. Drwg. 75	Print Fig.	Total Claims 115
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.	_____ (Assistant Examiner) _____ (Date)		NOTICE OF ALLOWANCE MAILED	
	<input checked="" type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S. Patent No. _____ _____ _____	<i>George Goudreau 7-03'</i> GEORGE GOUDREAU PRIMARY EXAMINER _____ (Primary Examiner) _____ (Date)		ISSUE FEE
Amount Due _____ Date Paid _____				
<input checked="" type="checkbox"/> The terminal _____ months of this patent have been disclaimed.	_____ (Legal Instruments Examiner) _____ (Date)		ISSUE BATCH NUMBER	
WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368. Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.				

Form PTO-436A

(Rev. 6/98)

FILED WITH: ☐ DISK (CRF) ☐ FICHE ☐ CD-ROM

(Attached in pocket on right inside flap)

(FACE)